

## ABSTRACT

In a cryo pump 20 that is used in a process chamber 10 into which a process gas is introduced and that includes a first-stage panel, a heat shield plate 24, and a second-stage panel 28, a notch for allowing for entrance of gas molecules and an additional shield 34 for preventing entrance of heat due to radiation from a room-temperature cryo pump chamber are provided in the heat shield plate 24. Thus, lowering of a performance of the cryo pump caused by the process gas getting between the cryo pump chamber and the heat shield plate can be prevented.